MICRON.272A PATENT

PARTICLE DETECTION METHOD

Abstract of the Disclosure

A method for detecting on a substrate used in the fabrication of integrated devices comprises the steps of (1) contacting the substrate with a monomer, wherein the particle catalyzes the polymerization of the monomer, and (2) detecting the particle using a particle counter. Different types of particles may be distinguished through their different polymerization rates of the monomer. Accordingly, in some certain embodiments, steps (1) and (2) may be repeated, allowing the growth rates of the particles to be determined. A plurality of monomers may be employed to identify different types of particles on the same substrate. The method is useful in detecting copper particles on silicon substrates.

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